



**INFORMATION DISCLOSURE CITATION**  
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Docket Number (Optional) TWI-6660	Application Number 10/797,163
Applicant(s) Jon Opsal et al.	
Filing Date March 10, 2004	Group Art Unit 2877

**U.S. PATENT DOCUMENTS**

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE

**FOREIGN PATENT DOCUMENTS**

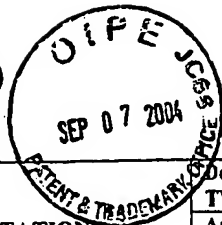
	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
<i>RW</i>	AA	WO 83/03303	09/29/1983	PCT	G01N	21/63		
<i>RW</i>	AB	0 432 963 A2	06/19/1991	EPC	G01N	21/17		

**OTHER DOCUMENTS**

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<i>RW</i>	AC	A. Rosencwaig, "Depth Profiling of Integrated Circuits with Thermal Wave Electron Microscopy," <i>Electronic Letters</i> , 20th Nov. 1980, Vol. 16, No. 24, pp. 928-930.
<i>RW</i>	AD	J. Opsal et al., "Thermal and plasma wave depth profiling in silicon," <i>Appl. Phys. Lett.</i> , 1 Sept. 1985, Vol. 47, No. 5, pp. 498-500.
<i>RW</i>	AE	A. Rosencwaig, Chapters 17, 18, and 21 <i>Photoacoustics and Photoacoustic Spectroscopy</i> , 1980, pp. 207-244 (Chapts. 17-18) and 270-284 (Chapt. 21).
<i>RW</i>	AF	X.D. Wu et al., "Photothermal microscope for high- $T_c$ superconductors and charge density waves," <i>Rev. Sci. Instrum.</i> , Nov. 1993, Vol. 64, No. 11, pp. 3321-3327.
<i>RW</i>	AG	J.T. Fanton et al., "High-sensitivity laser probe for photothermal measurements," <i>Appl. Phys. Lett.</i> , 13 July 1987, Vol. 51, No. 2, pp. 66-68.
<i>RW</i>	AH	J.T. Fanton et al., "Low-Temperature Photothermal Measurements of High $T_c$ Superconductors," <i>The Review of Progress in Quantitative Nondestructive Evaluation</i> (Reprint G.L. Report No. 4728 [Aug. 1990]), Presented July 15-20, 1990, 8 pages in length.
<i>RW</i>	AI	B.C. Forget et al., "Electronic diffusivity measurement in silicon by photothermal microscopy," <i>Appl. Phys. Lett.</i> , 19 Aug. 1996, Vol. 69, No. 8, pp. 1107-1109.
<i>RW</i>	AJ	J.T. Fanton et al., "Multiparameter measurements of thin films using beam-profile reflectometry," <i>Journal of Applied Physics</i> , 1 June 1993, Vol. 73, No. 11, pp. 7035-7040.
<i>RW</i>	AK	G. Langer et al., "Thermal conductivity of thin metallic films measured by photothermal profile analysis," <i>Rev. Sci. Instrum.</i> , Vol. 68 (3), March 1997, pp. 1510-1513.
<i>RW</i>	AL	G. Savignat et al., "Non-destructive characterization of refractories by mirage effect and photothermal microscopy," <i>Journal De Physique IV, Colloque C7, supplement au Journal de Physique III</i> , Vol. 3, Nov. 1993, pp. 1267-1272.
<i>RW</i>	AM	M.B. Suddendorf et al., "Noncontacting measurement of opaque thin films using a dual beam thermal-wave probe," <i>Appl. Phys. Lett.</i> , Vol. 62 (25), 21 June 1993, pp. 3256-3258.
<i>RW</i>	AN	M. Liu et al., "Response of interferometer based probe systems to photodisplacement in layered media," <i>J. Appl. Phys.</i> , Vol. 76 (1), 1 July 1994, pp. 207-215.
<i>RW</i>	AO	J.F. Bisson et al., "Influence of diffraction on low thermal diffusivity measurements with infrared photothermal microscopy," <i>J. Appl. Phys.</i> , Vol. 83 (2), 15 January 1998, pp. 1036-1042.
<i>RW</i>	AP	E.P. Visser et al., "Measurement of thermal diffusion in thin films using a modulated laser technique: Application to chemical-vapor-deposited diamond films," <i>J. Appl. Phys.</i> , Vol. 71 (7), 1 April 1992, pp. 3238-3248.
<i>RW</i>	AQ	L. Pottier, "Micrometer scale visualization of thermal waves by photorefectance microscopy," <i>Appl. Phys. Lett.</i> , Vol. 64 (13), 28 March 1994, pp. 1618-1619.
<i>RW</i>	AR	A.M. Mansanares et al., "Photothermal microscopy: Thermal contrast at grain interface in sintered metallic materials," <i>J. Appl. Phys.</i> , Vol. 75 (7), 1 April 1994, pp. 3344-3350.

Examiner <i>John W. L.</i>	Date Considered 19 NOV. 2004
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

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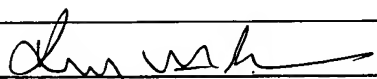
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							YES	NO

**OTHER DOCUMENTS**

(Including Author, Title, Date, Pertinent Pages, Etc.)

	AS	A.M. Mansanares et al., "Temperature field determination of InGaAsP/InP lasers by photothermal microscopy: Evidence for weak nonradiative processes at the facets," <i>Appl. Phys. Lett.</i> , Vol. 64 (1), 3 January 1994, pp. 4-6.
	AT	Jian-Chun Cheng et al., "Theoretical studies of pulsed photothermal phenomena in semiconductors," <i>J. Appl. Phys.</i> , Vol. 74, No. 9, 1 November 1993, pp. 5718-5725.

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Date Considered

19 Nov. 2004

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